

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE  
WASHINGTON, D.C. 20231

Inventor: **Lynn Forester**

Serial No: **Div. of 09/860993**

Filed: **May 17, 2001**

For: **Layered Hard Mask and  
Dielectric Materials and  
Methods Therefor**

Examiner: **Travis Ribar**

Art Unit: **1711**

**PRELIMINARY AMENDMENT**

Mail Stop Patent Application  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

Please enter the following preliminary amendment:

**IN THE CLAIMS**

Please cancel all allowed claims and add the following claims addressing subject matter in application serial number 09/860993:

Claim 21: (Added) A layered material, comprising:

a hard mask layer, and

a line dielectric layer, wherein the hard mask layer is applied in a liquid phase to a line dielectric layer, wherein the hard mask layer comprises a Si-N bond, and wherein the hard mask layer is densified such that the hard mask has an etch resistivity that is greater than an etch resistivity of the line dielectric layer.